

WHAT IS CLAIMED IS:

1. A mask structure, comprising:

a transparent substrate;

a cover layer, formed on the transparent substrate and provided with exposure
5 patterns; and

a transparent conductive thin film, with which the cover layer and the transparent
substrate is covered.

2. The mask structure according to claim 1, wherein the mask structure further
comprises a ground line connected to an edge of the transparent conductive thin film.

10 3. The mask structure according to claim 1, wherein the transparent conductive thin
film is made of palladium aluminum oxide.

4. The mask structure according to claim 1, wherein the cover layer is made of
chromium.

15 5. The mask structure according to claim 1, wherein the transparent substrate can be
made of quartz.

6. The mask structure according to claim 1, wherein the transparent substrate is made
of calcium fluoride.

7. A process of fabricating a mask, comprising the steps of:

forming a cover layer provided with exposure patterns on a transparent substrate;

20 and

covering the transparent substrate and the cover layer uniformly with a transparent
conductive thin film.

8. The process of fabricating a mask according to claim 7, wherein a ground line
connected to an edge of the transparent conductive thin film.

9. The process of fabricating a mask according to claim 7, wherein the transparent conductive thin film is made of palladium aluminum oxide.

10. A mask structure, comprising:

a transparent substrate;

5 a transparent conductive thin film formed on the transparent substrate; and

a cover layer, formed on the transparent conductive thin film and provided with exposure patterns.

11. The mask structure according to claim 10, wherein the mask structure further comprises a ground line connected to an edge of the transparent conductive thin film.

10 12. The mask structure according to claim 10, wherein the transparent conductive thin film is made of palladium aluminum oxide.

13. The mask structure according to claim 10, wherein the cover layer is made of chromium.

14. The mask structure according to claim 10, wherein the transparent substrate can be
15 made of quartz.

15. The mask structure according to claim 10, wherein the transparent substrate is made of calcium fluoride.

16. A process of fabricating a mask, comprising the steps of:

forming a transparent conductive thin film on a transparent substrate; and

20 forming a cover layer provided with exposure patterns on the transparent conductive thin film.

17. The process of fabricating a mask according to claim 16, wherein a ground line connected to an edge of the transparent conductive thin film.

18. The process of fabricating a mask according to claim 16, wherein the transparent

conductive thin film is made of palladium aluminum oxide.

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